

# WAFER PROBER

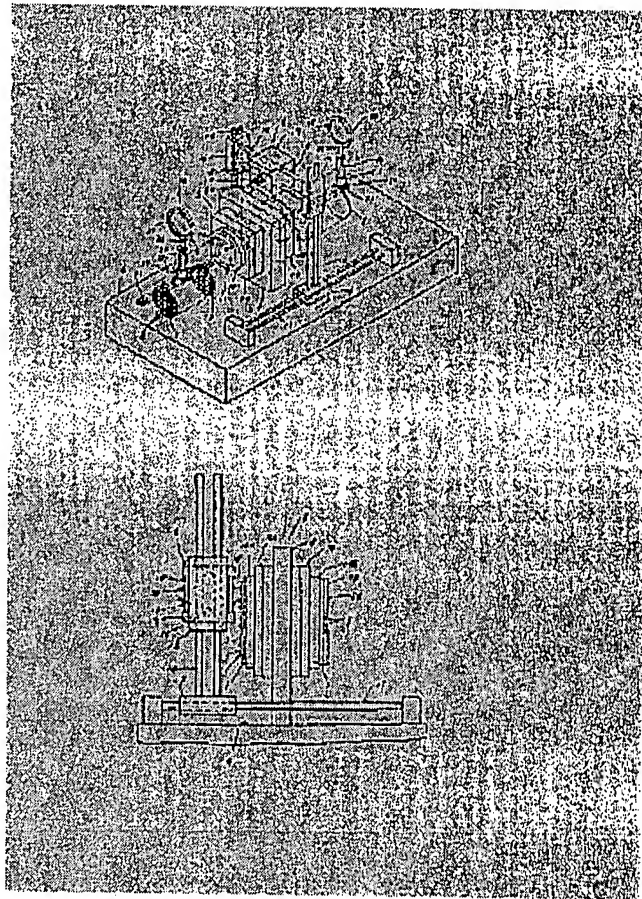
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## Abstract of JP62098634

**PURPOSE:** To suppress an expanding of the occupation area of a wafer prober, which occurs along with an increase in the diameter of a wafer, by a method wherein the probing stage is so constituted as to hold wafers in a vertical state and the probing block is so constituted as to bring the probes into contact with the wafer from the horizontal direction.

**CONSTITUTION:** A wafer prober is provided with a base 4 and a probing stage 5, a probing block 6 and two groups of handlers 17A and 17B are installed on the base 4. The probing stage 5 is provided with a support 8 being formed in a roughly square flat board and the support 8 is arranged at the almost central part of the upper surface of the base 4 and is vertically erected in such a way that its both ends face right and left. A plurality of pieces of attracting holes 11 are openly provided in each theatable 10A and 10B and the attracting holes 11 are so constituted as to hold a wafer 1 in a vertical state by vacuum-attracting it. Window holes 19 are each openly provided in probe cards 18 in such a way as to be arranged at the roughly central part of each card and a plurality of probes 20 are protruded on the periphery of each window hole 19 radially in such a way as to turn toward the center of the window hole 19 and also slantingly in the opposite direction to the direction to a main body 17.



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